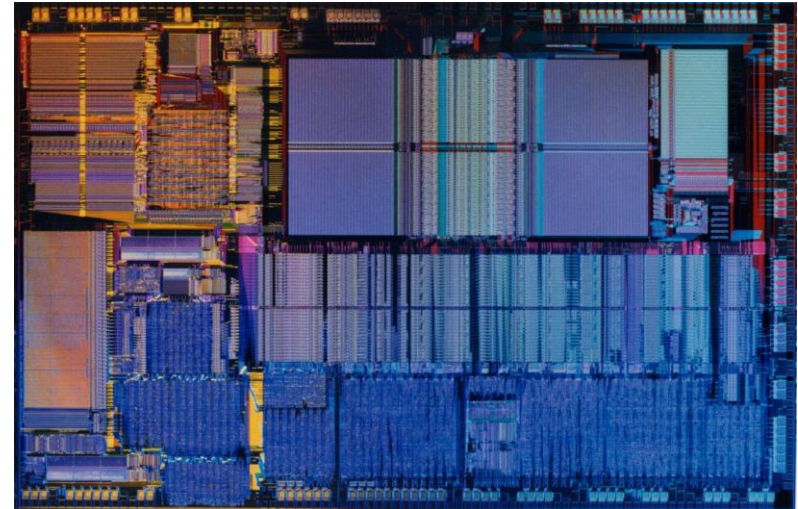
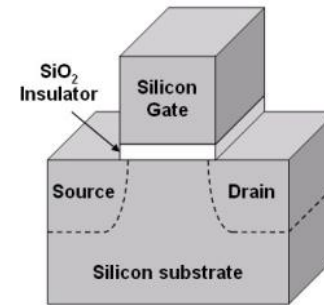


Too hot to handle? The emerging Challenge of Reliability/Variability in Self-heated FinFET, ETSOI, and GAA-FET

Muhammad A. Alam (alam@purdue.edu)
S. Shin, A. Wahab, J. Gu. J. Zhang, P. Ye

<http://nanohub.org/resources/16560>
cobweb.ecn.purdue.edu/~alam

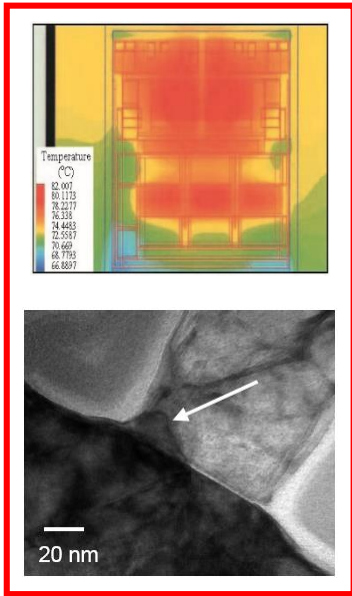
Uniformity of Components in Large Systems



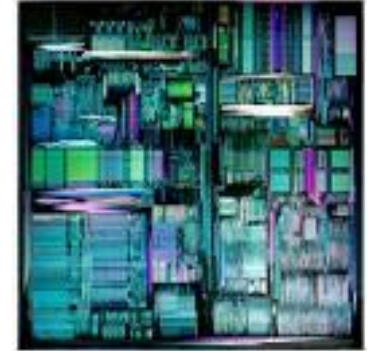
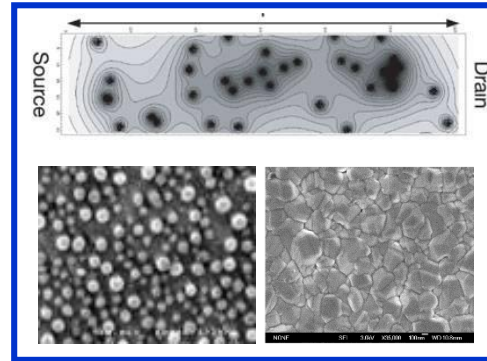
Building large systems presumes uniformity of components ...

Process, Reliability, and Design

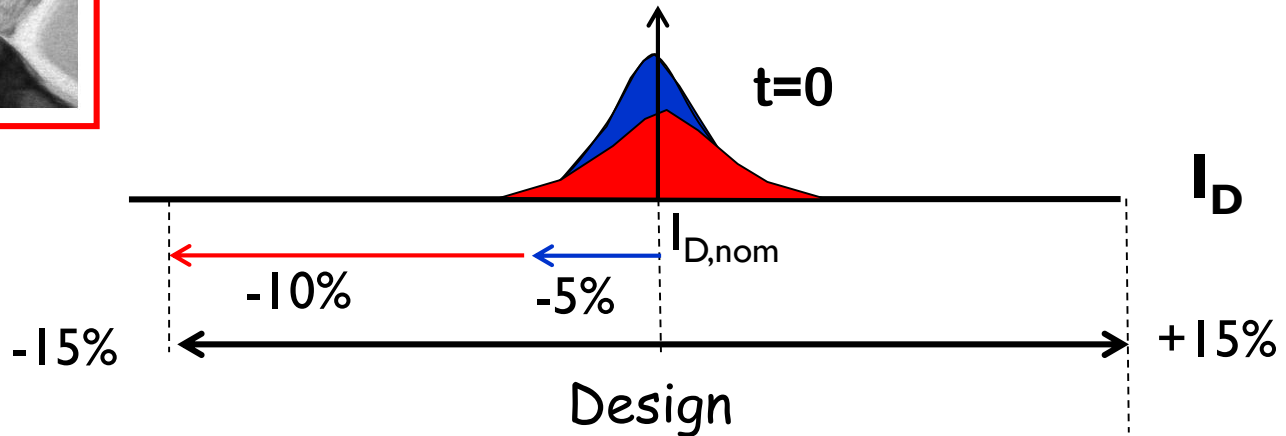
Reliability



Process



plus



We do not have too much margin ...

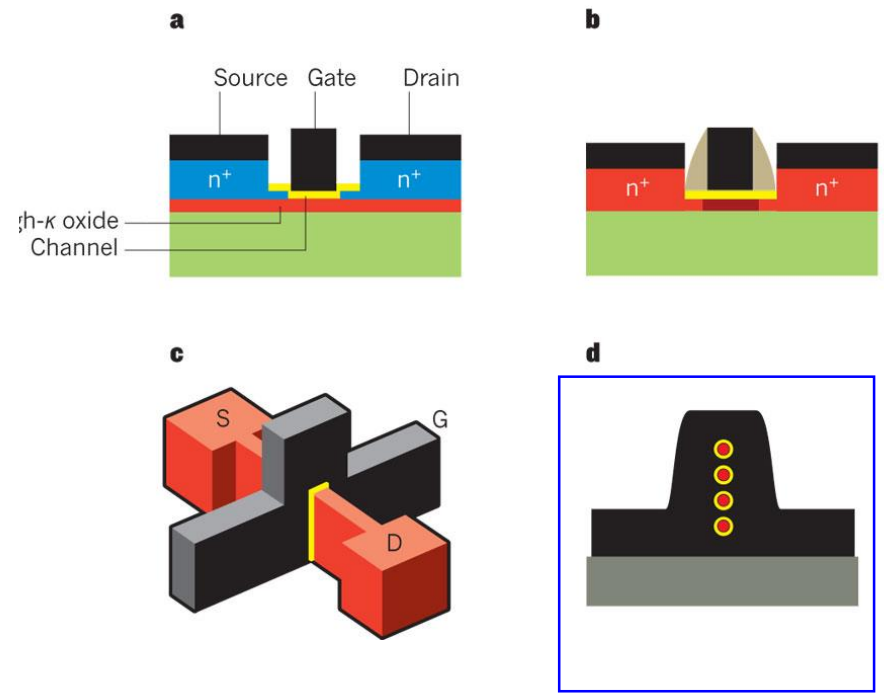
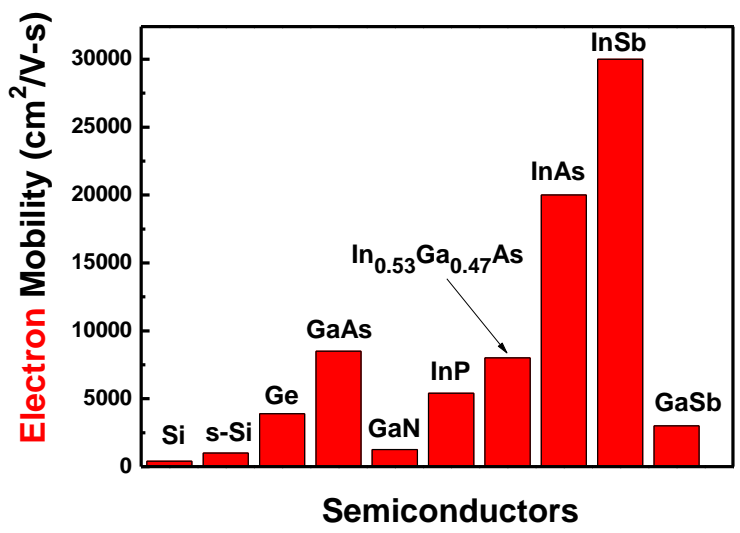
Outline

- Background: Variability/Reliability in Planar Transistors
- Self-heating in SG-FETs: An Emerging Issue
- Channel Width/Length dependence
- Reliability correlated to Variability: New Channels for MOSFET Degradation
- Conclusions

Emergence of Surround Gate Transistors Technologies

$$I_{on} \propto C_{ox} \mu_n (V_G - V_T)$$

$$I_{off} \propto I_o e^{\frac{q(V_G + \eta V_D)}{kT}}$$

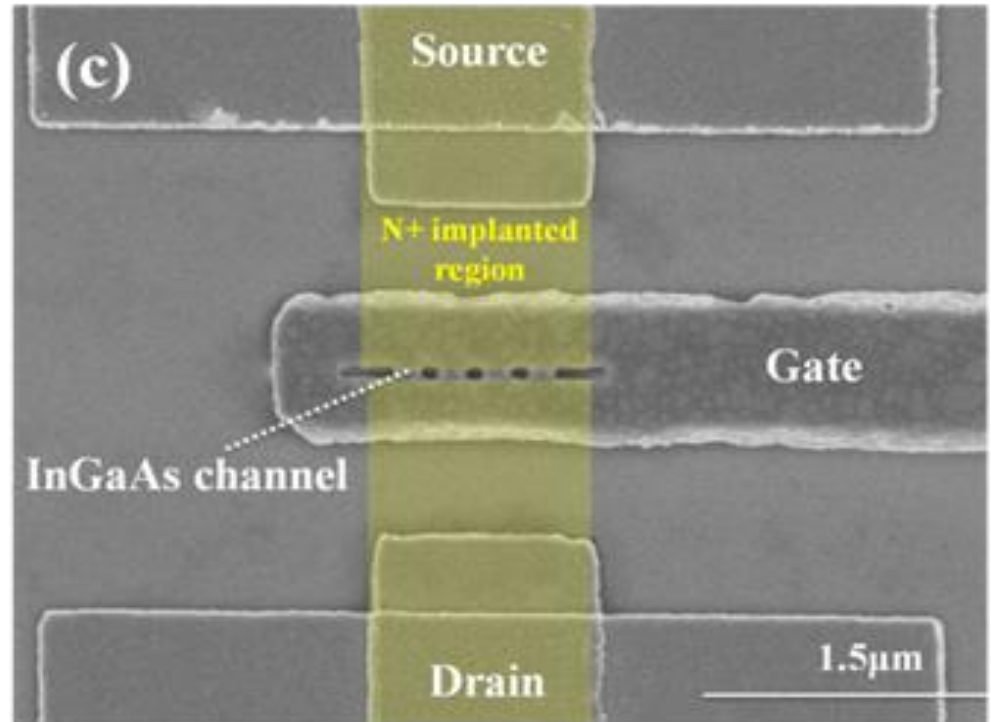
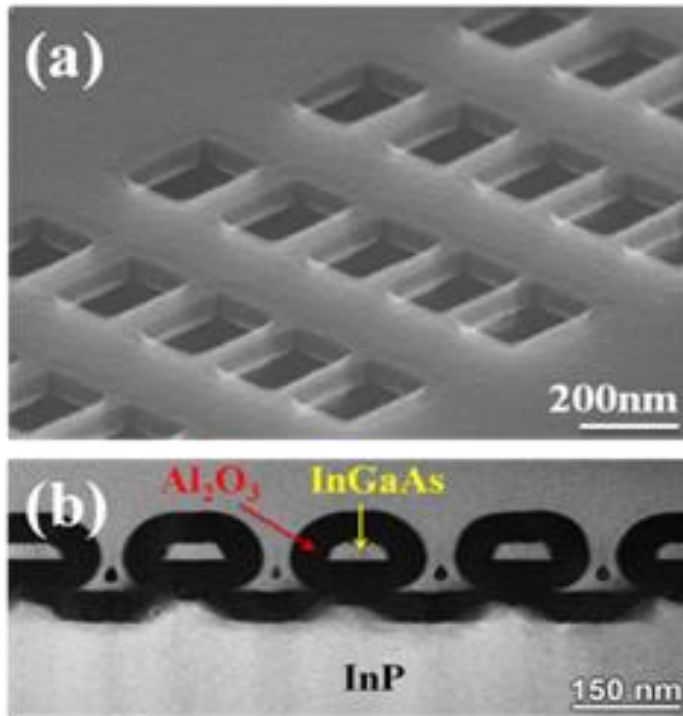


Extraordinary mobility

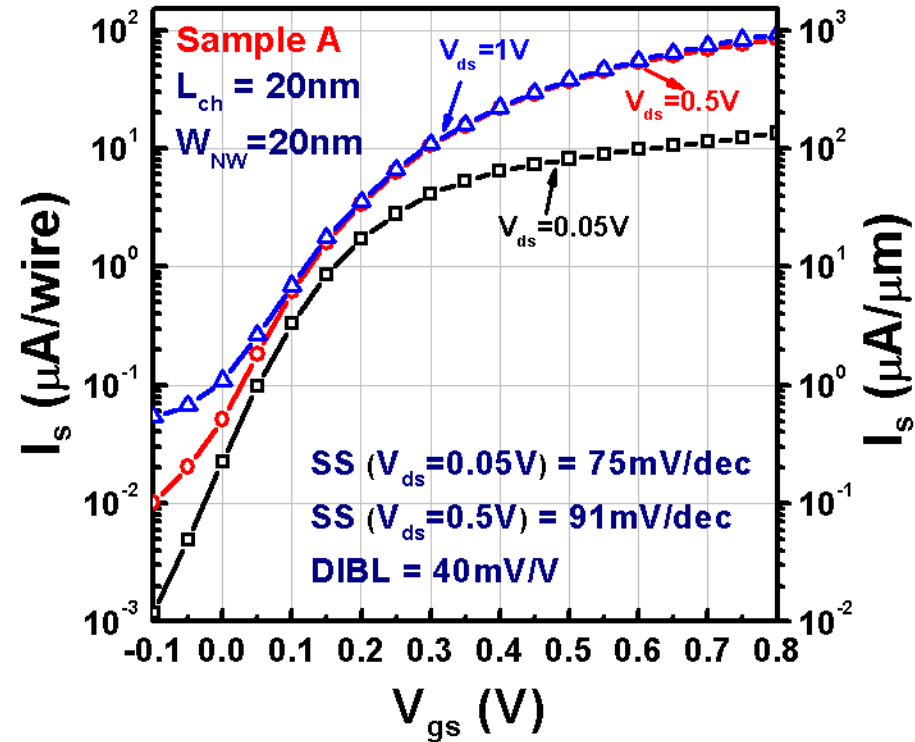
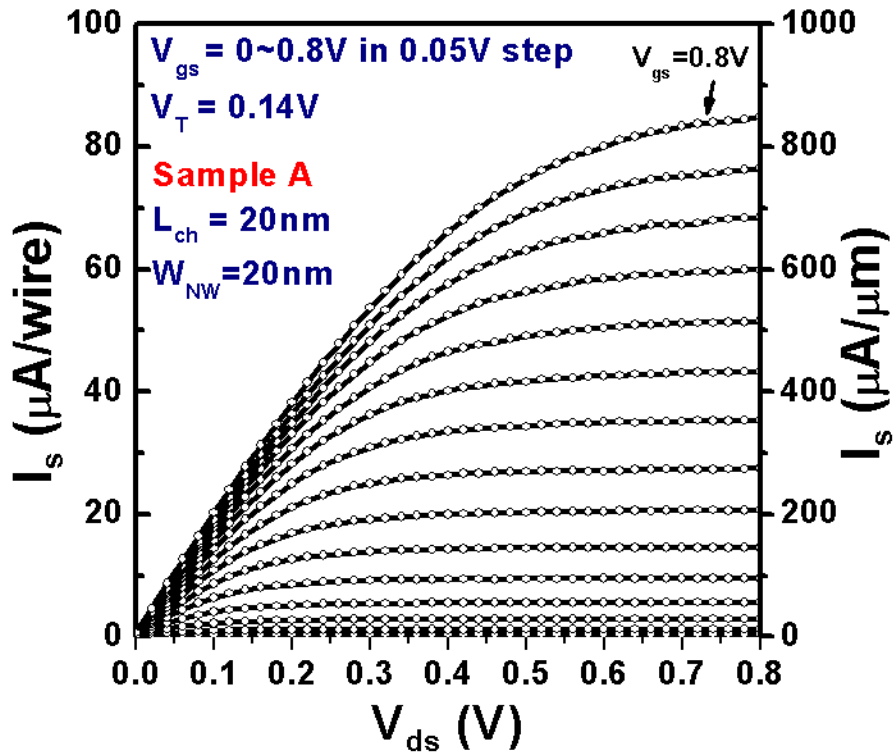
Excellent gate control

A Very High Performance MOSFET

Jiangjiang Gu, IEDM 2012



Performance is classical ...

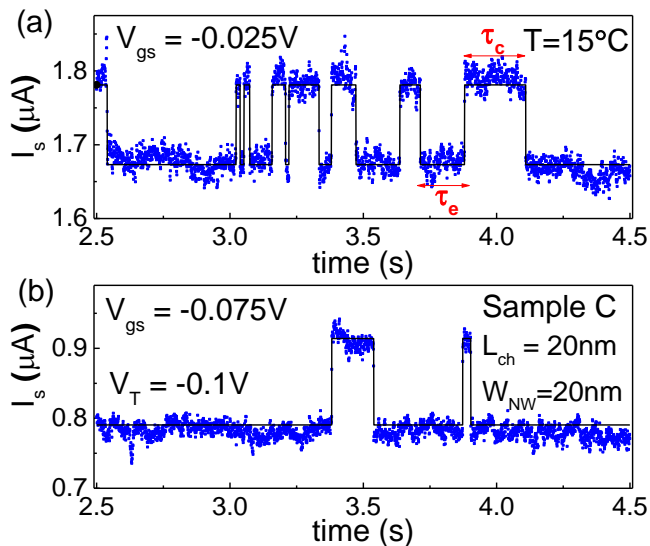


□ $L_{ch} = 20\text{nm}$, $EOT = 1.2\text{ nm}$,

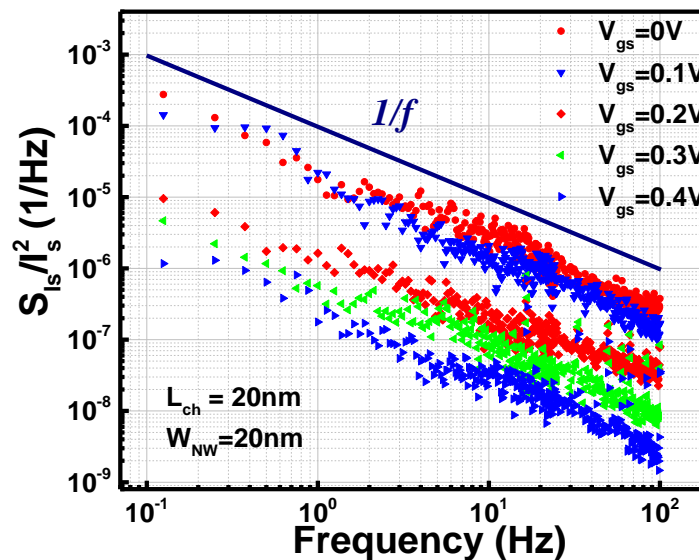
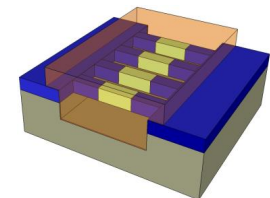
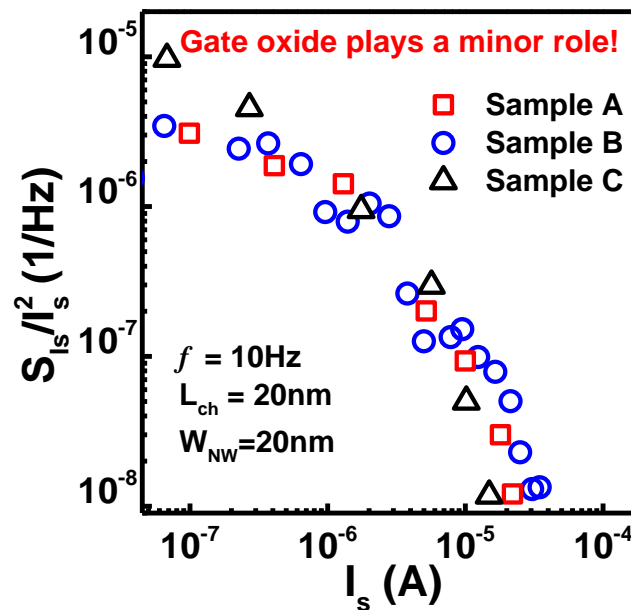
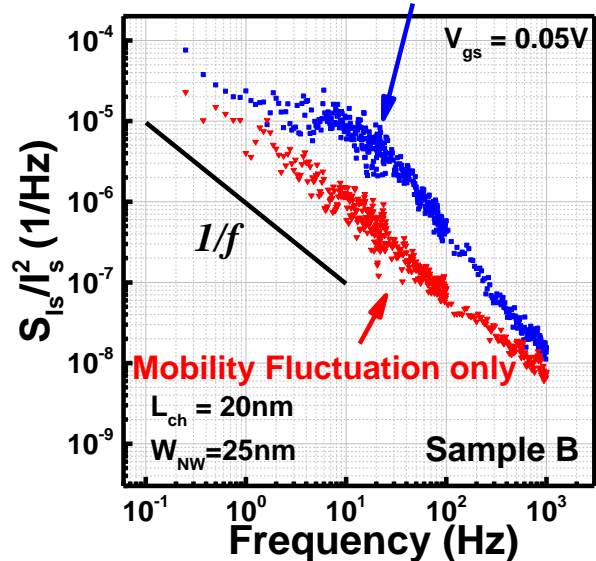
□ $I_{ON} = 0.57\text{mA}/\mu\text{m}$, $g_m = 1.65\text{mS}/\mu\text{m}$ @ $V_{ds} = V_{gs} - V_T = 0.5\text{V}$

□ $SS = 75\text{mV/dec}$, $DIBL = 40\text{mV/V}$, $V_{T,lin} = 0.14\text{V}$

... with good noise performance

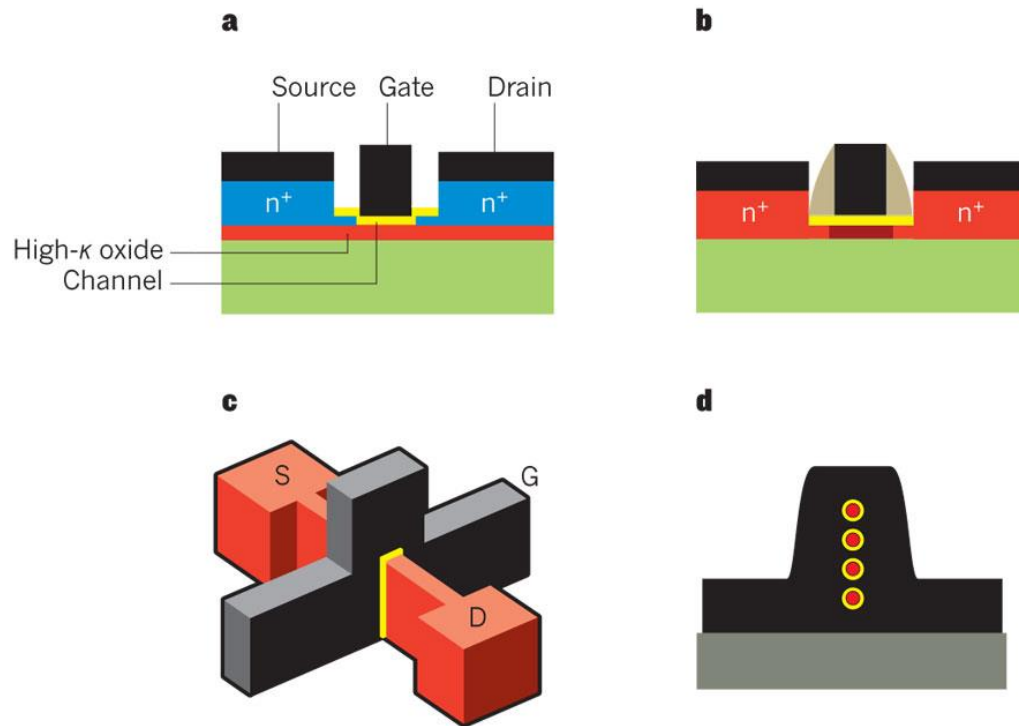


(RTN+Mobility Fluctuation)

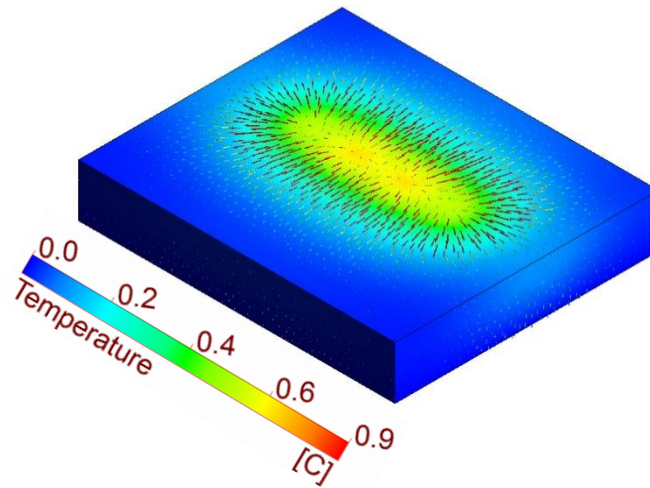
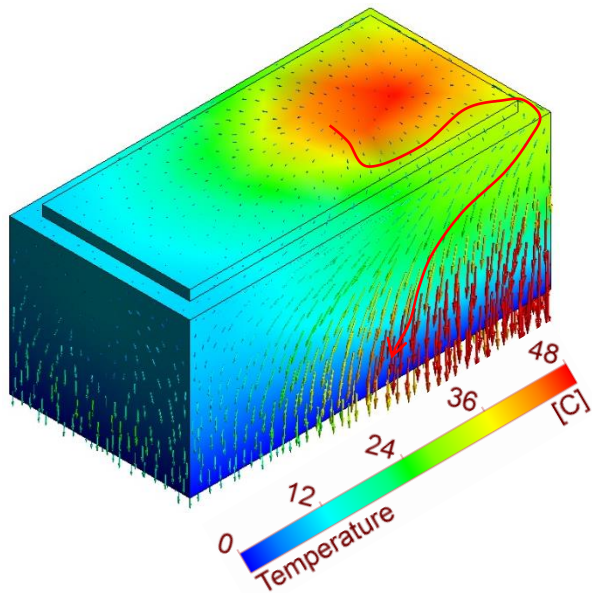
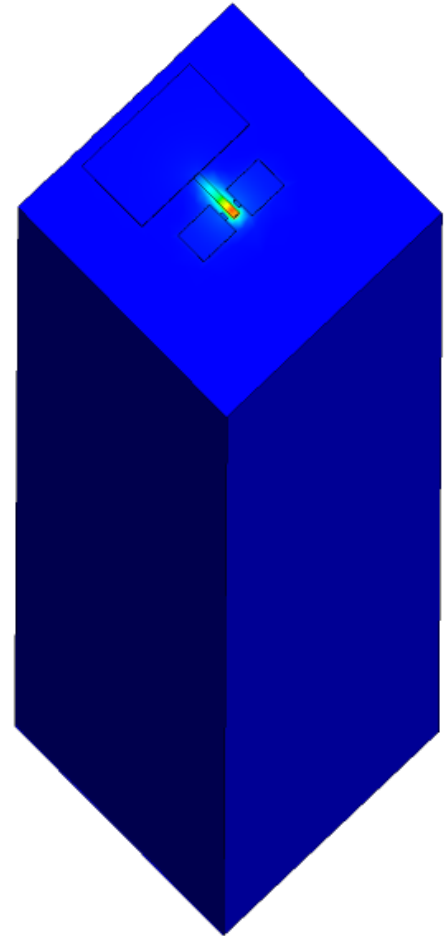
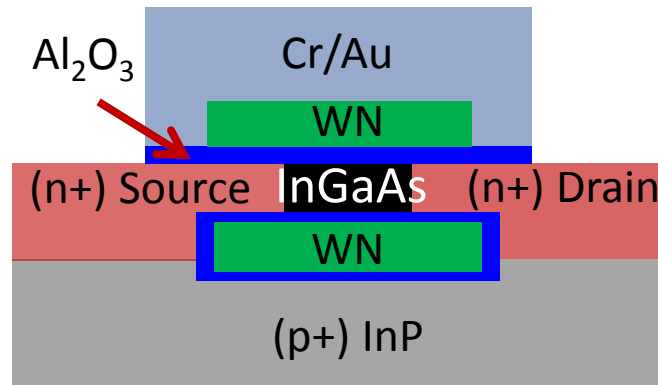
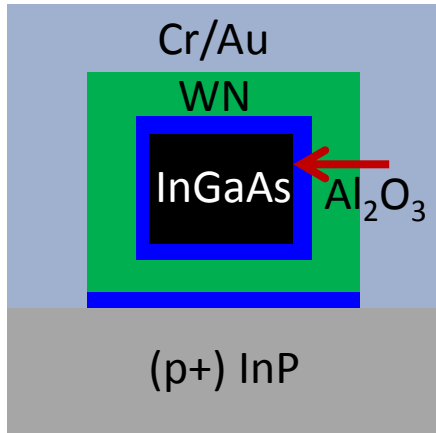


Power vs. self-heating

$$\Delta T \equiv T - T_a = P \times R_{th}$$

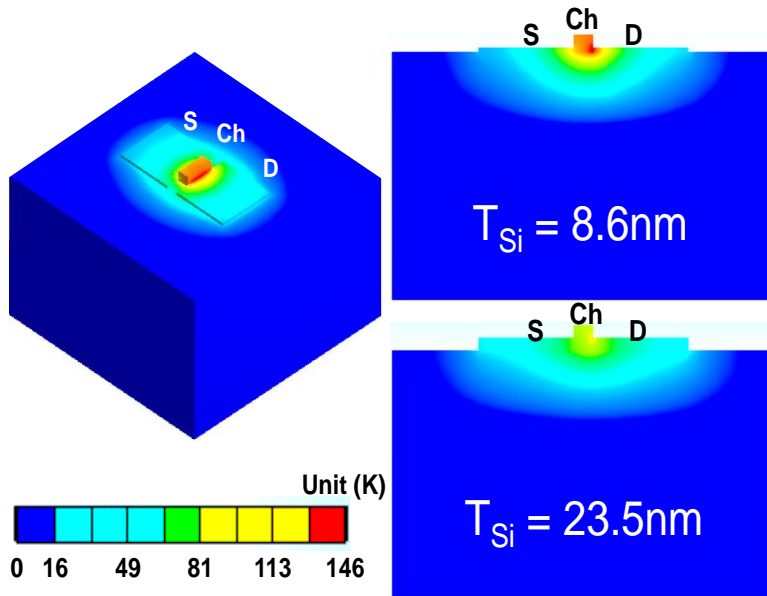


Process complexity & Thermal Bottleneck

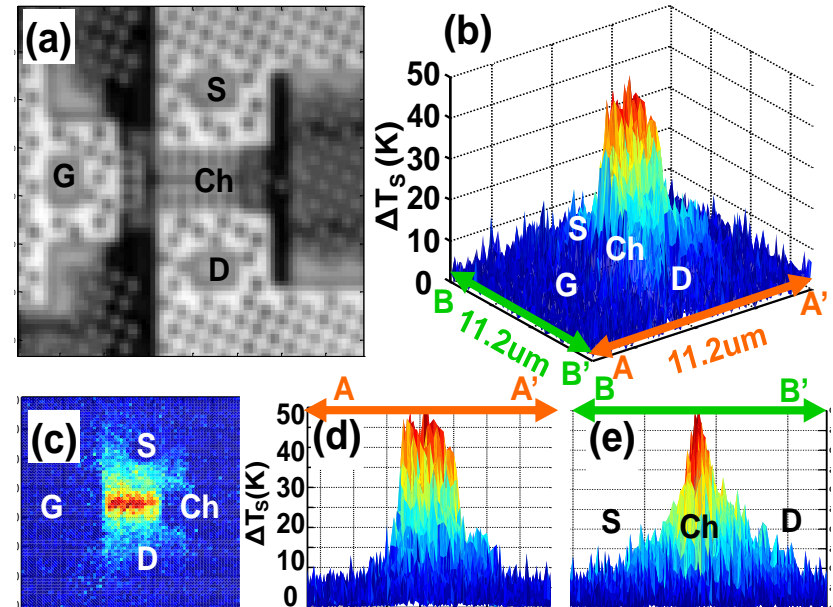


Self-heating and body thickness

Simulation

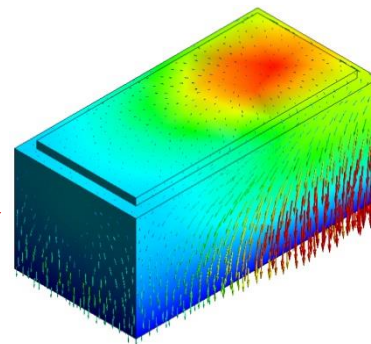
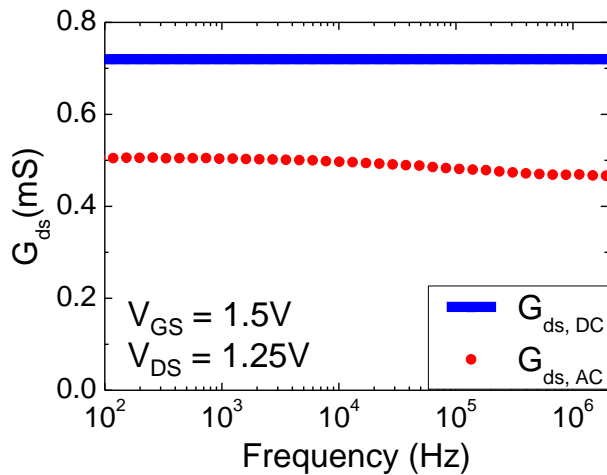
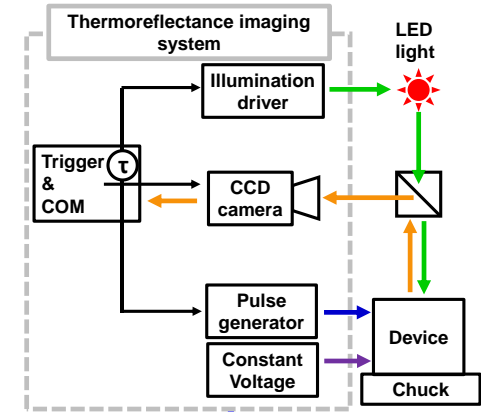
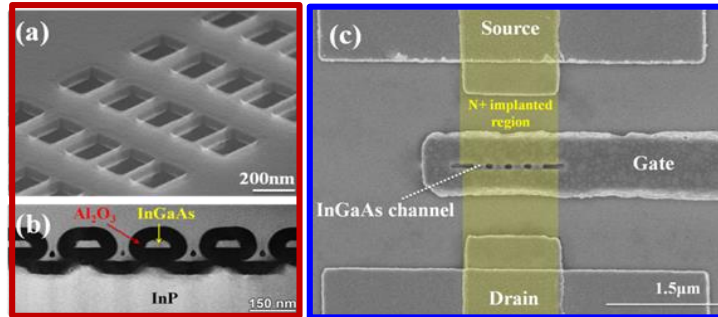
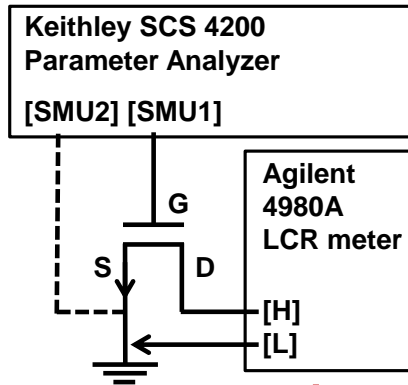


Experiment

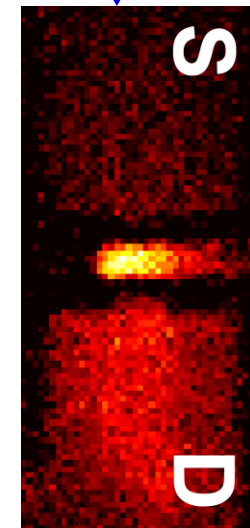


$$\Delta T \equiv T - T_a = P \times R_{th}$$

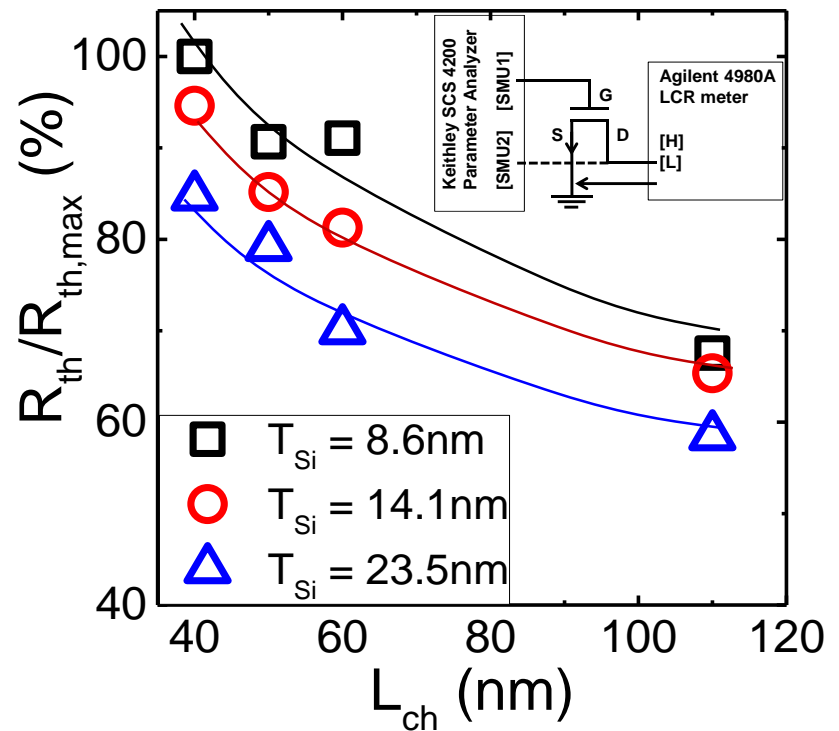
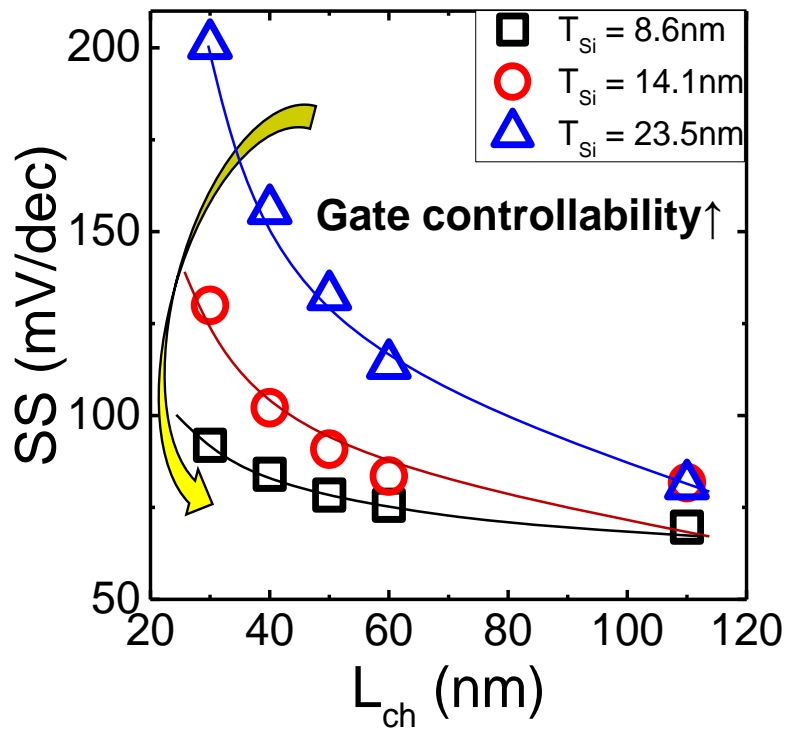
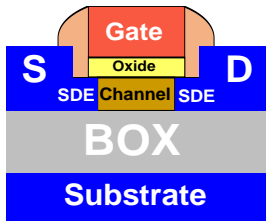
3D Mapping of Self-heating



Correlate by
modeling



Gate control vs. self-heating



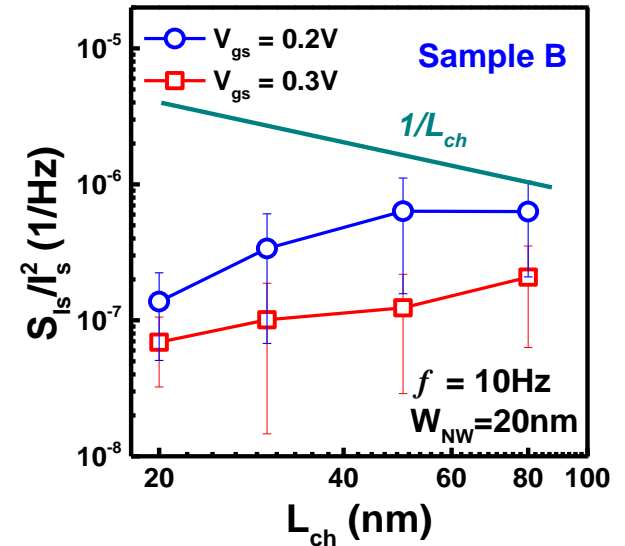
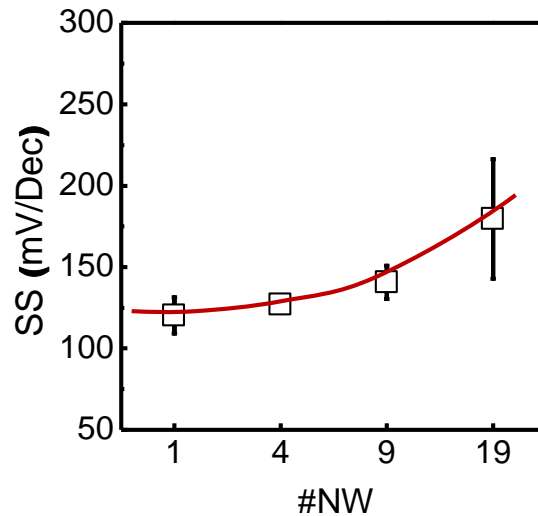
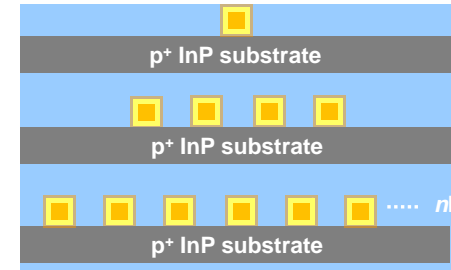
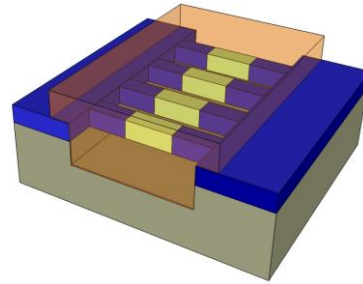
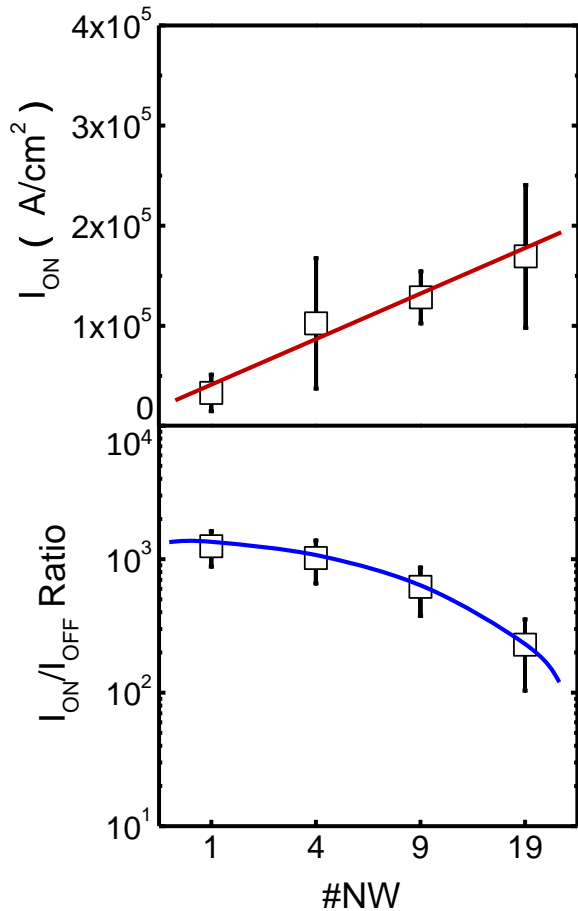
Improved SS comes with higher R_{th}

Outline

- Background: Variability/Reliability in Planar Transistors
- Self-heating in SG-FETs: An Emerging Issue
- Channel Width/Length dependence
- Reliability correlated to Variability: New Channels for MOSFET Degradation
- Conclusions

What is wrong with this picture ?

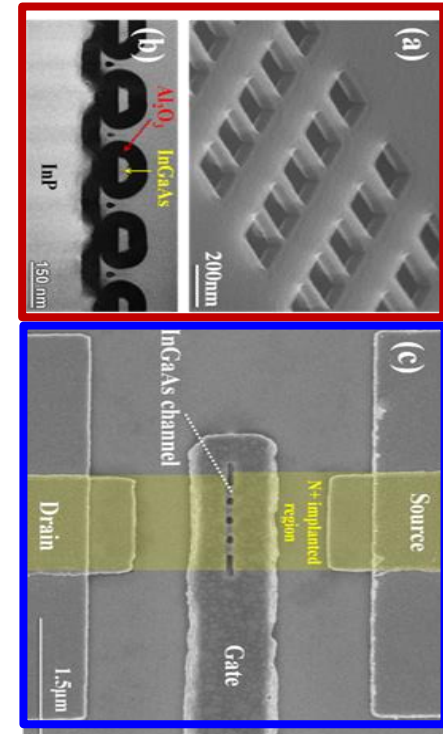
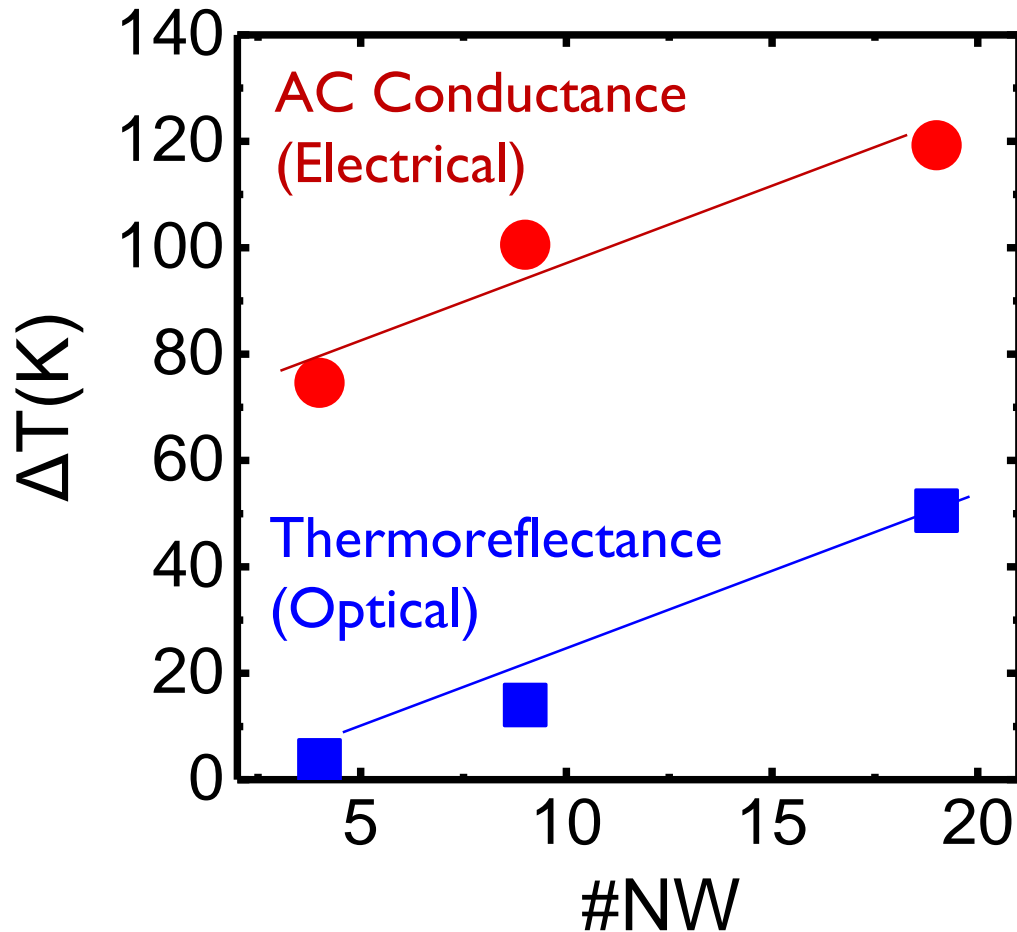
(1) On current does not scale



(2) Variable on/off ratio & SS slope..

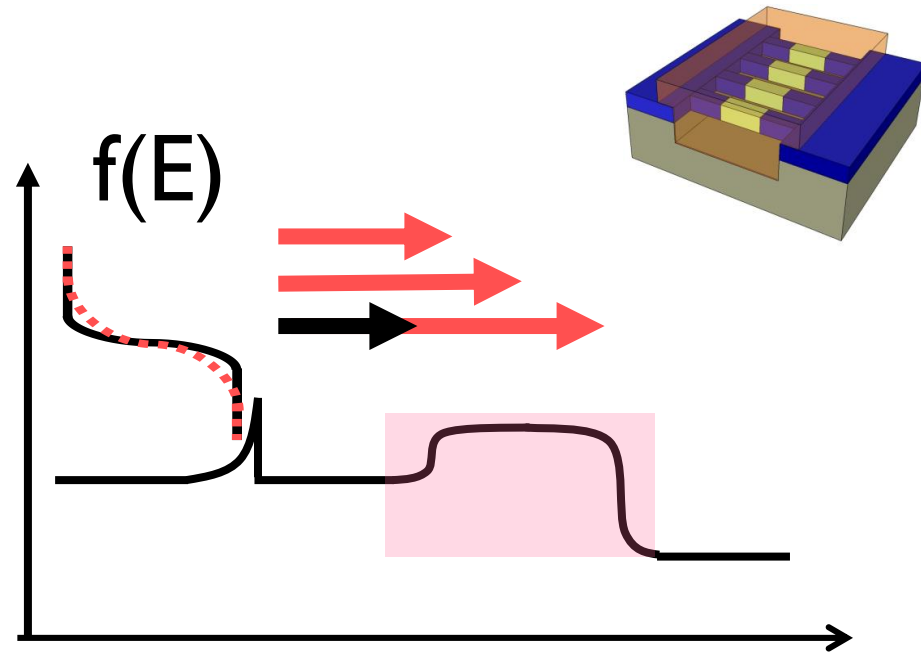
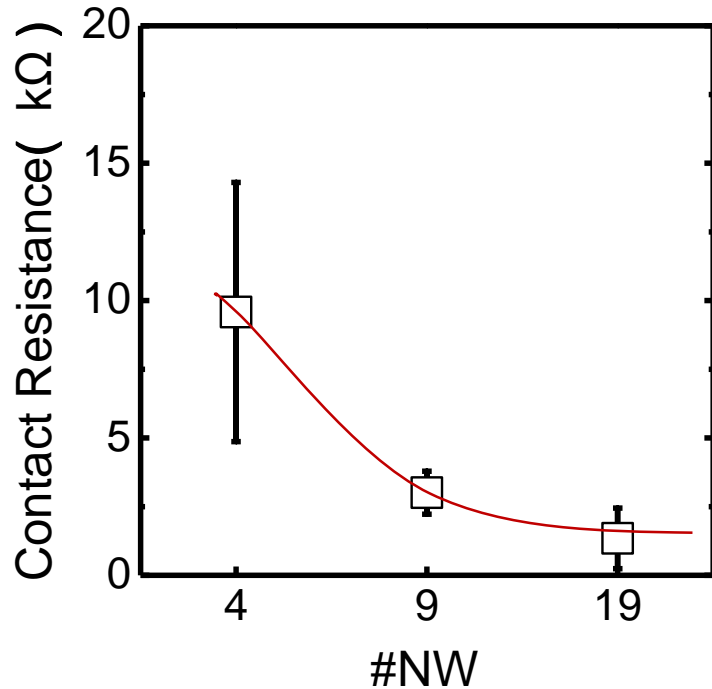
(3) Noise reduces with Lch!

Evidences of Significant Self-heating



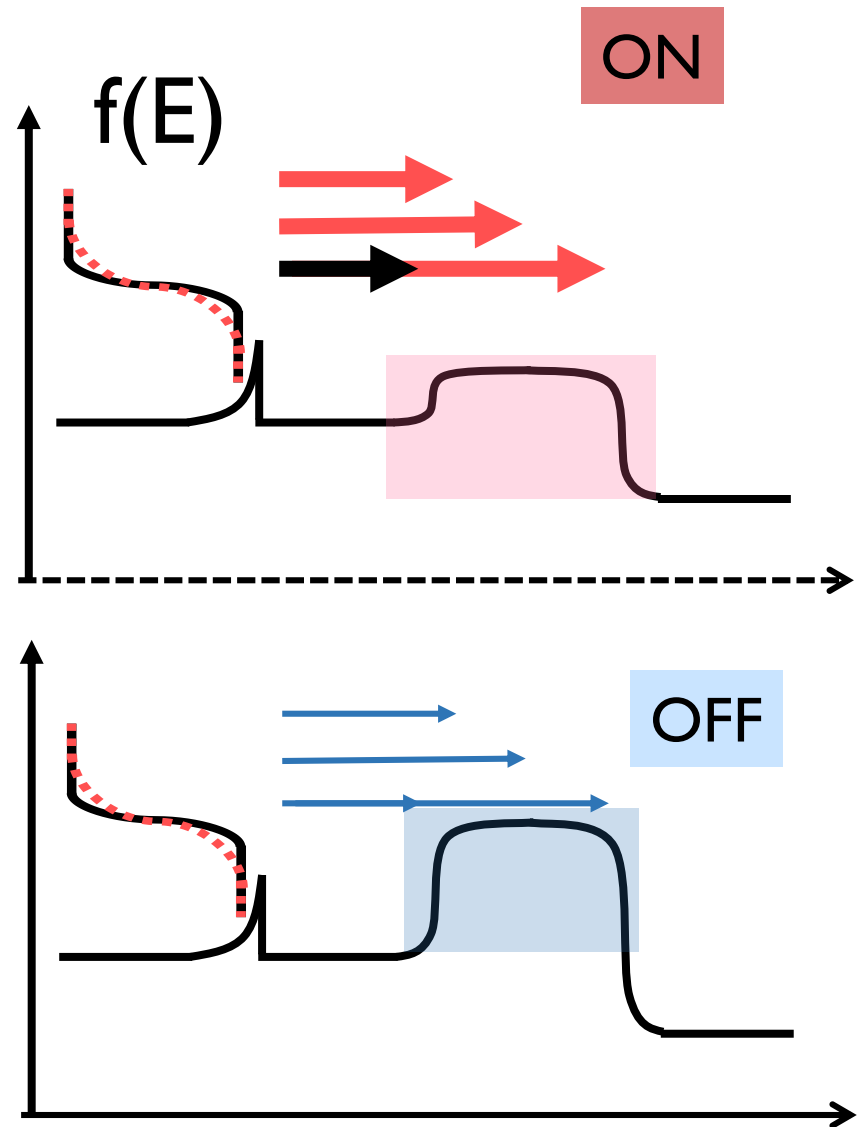
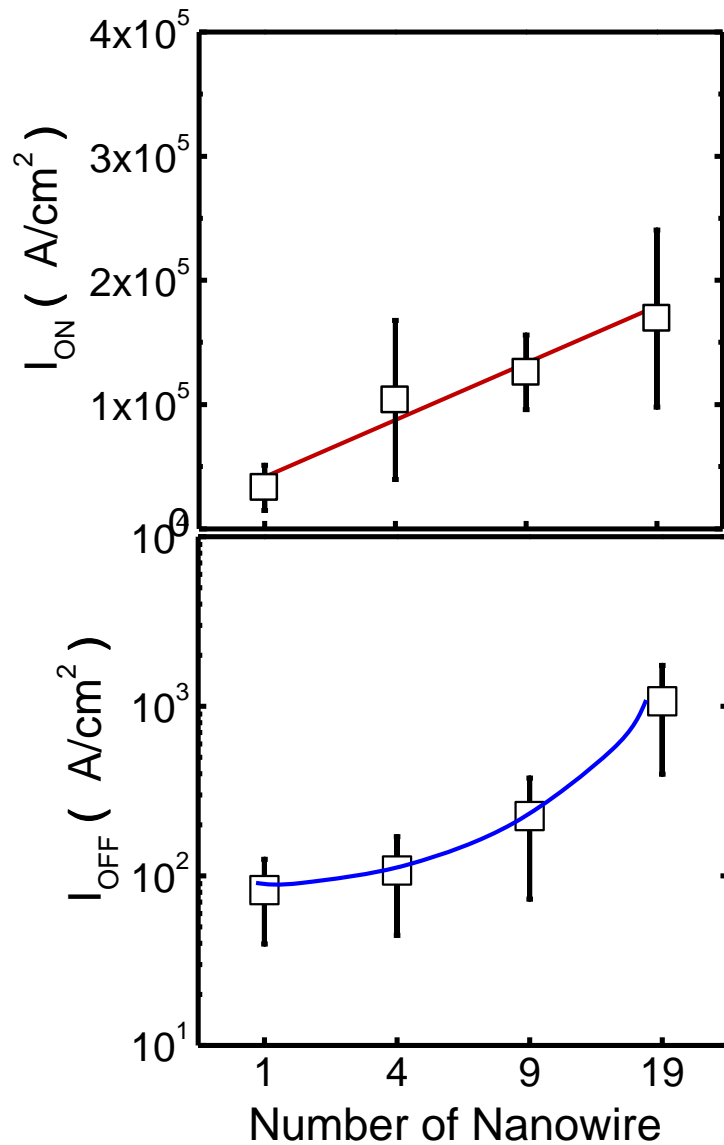
(4) Self heating (80-120), Surface T = 60-70 lower. **Why?**

Self heating reduces series resistance!

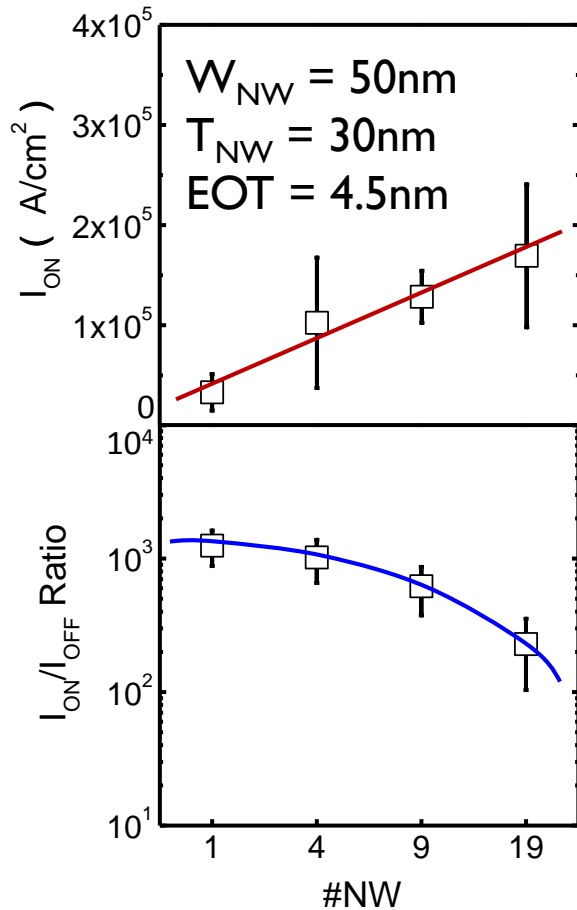


- Self-heating improves performance by reducing R_C , and hence improves I_{on} .
- Temperature dependence of channel resistance has the opposite sign.

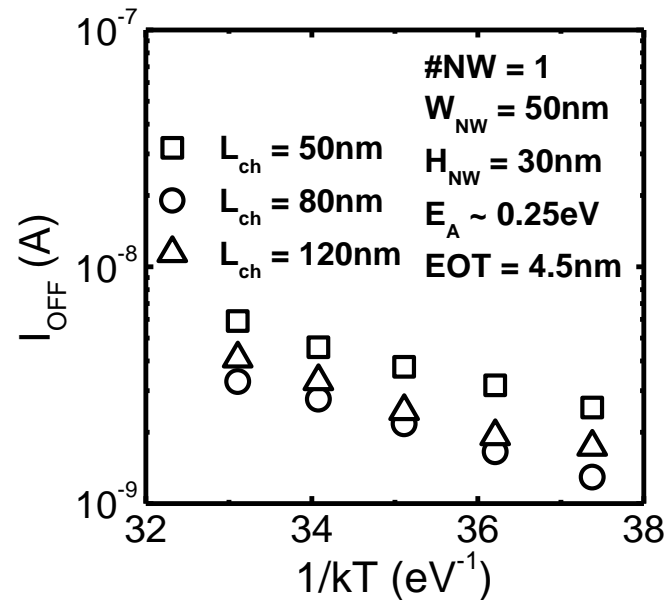
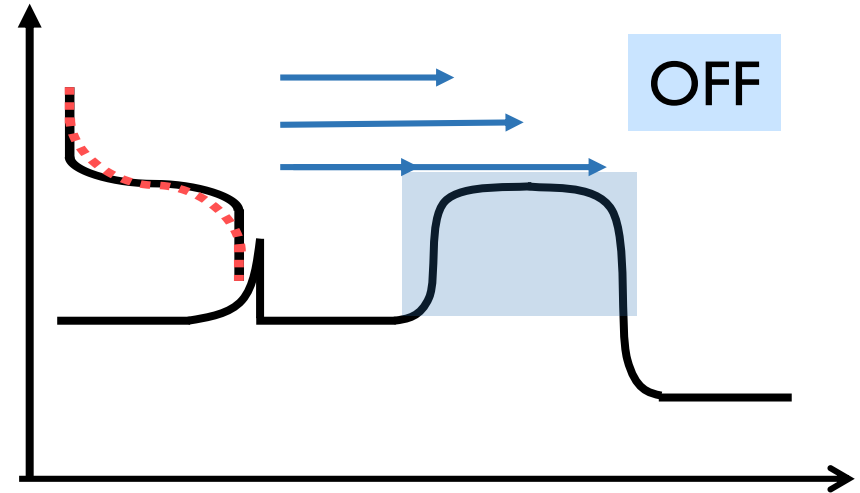
Self-heating for On & Off currents



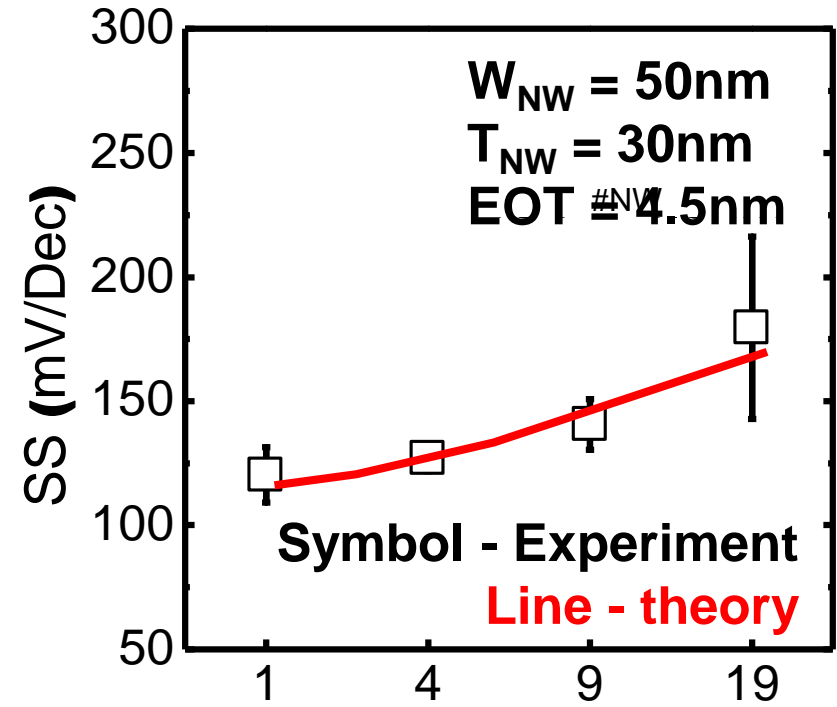
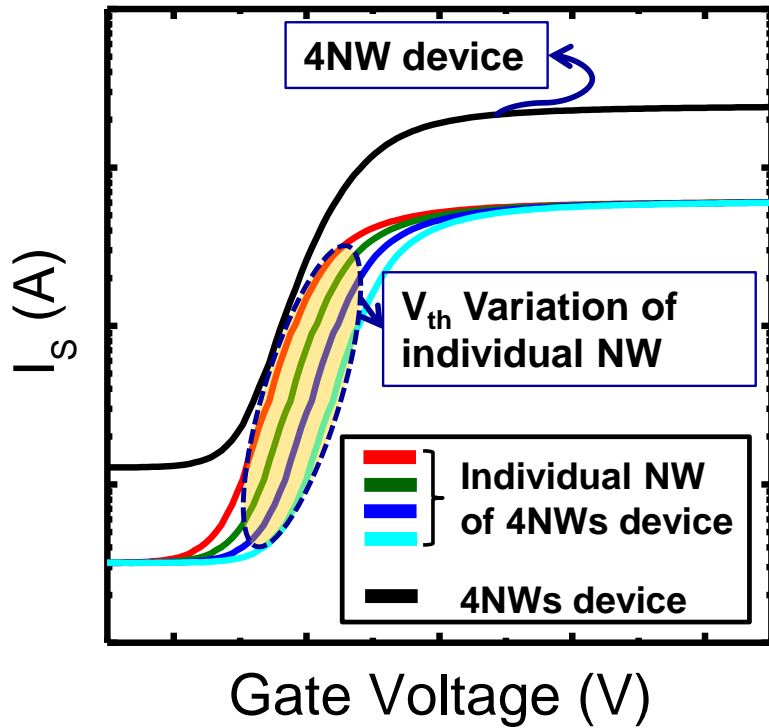
Self-heating explains on/off puzzle



Variable on off ratio ..



SS depends on Variability/Self-heating

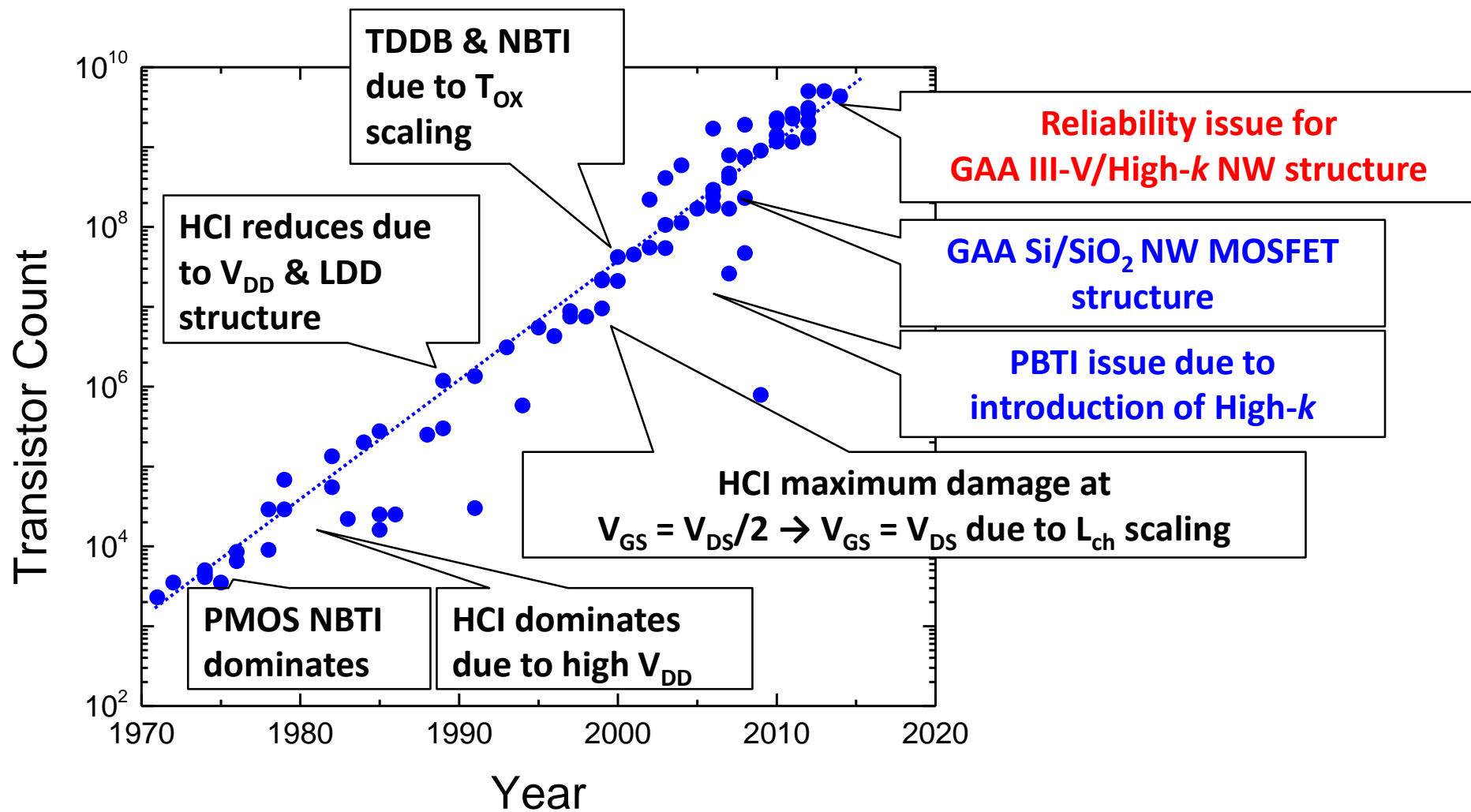


- I_s - V_{gs} of 4NW = summation of $4 \cdot (I_s$ - V_{gs} of 1NW)
- 4NW with variability of V_{th} \rightarrow Widening I_s - V_{gs}
- SS increases with Variability & Self heating

Outline

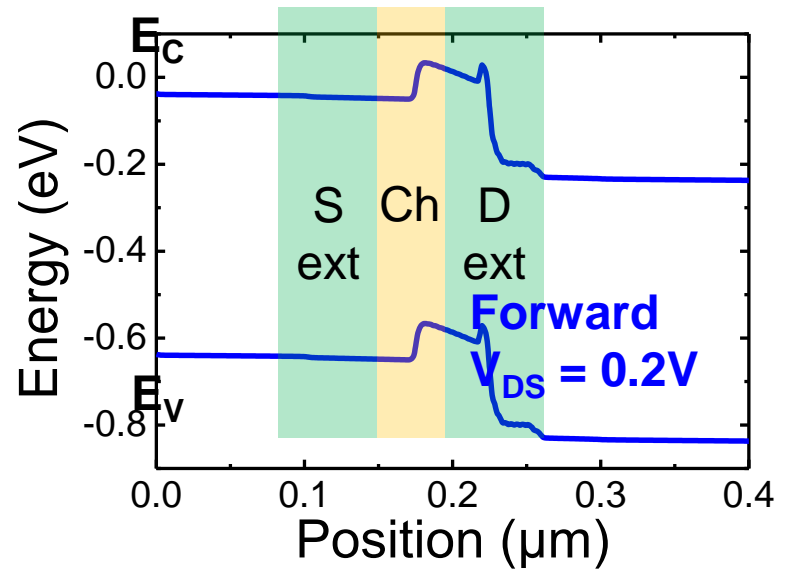
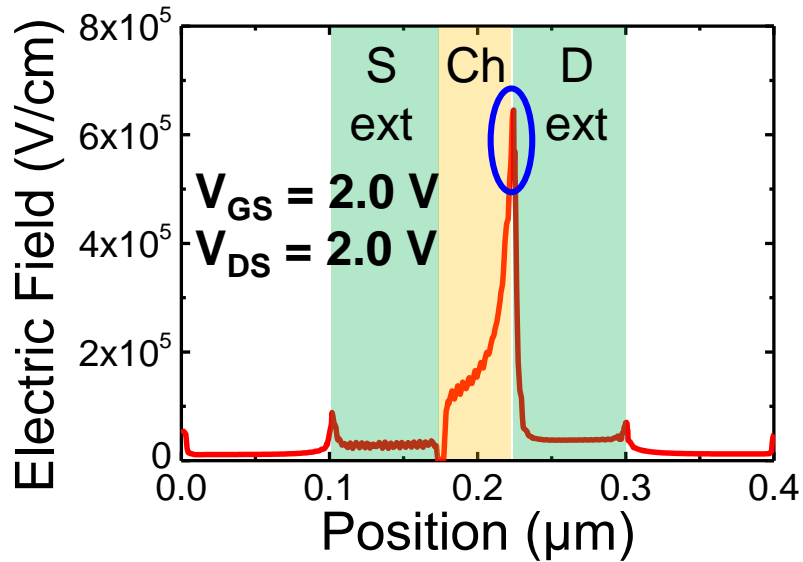
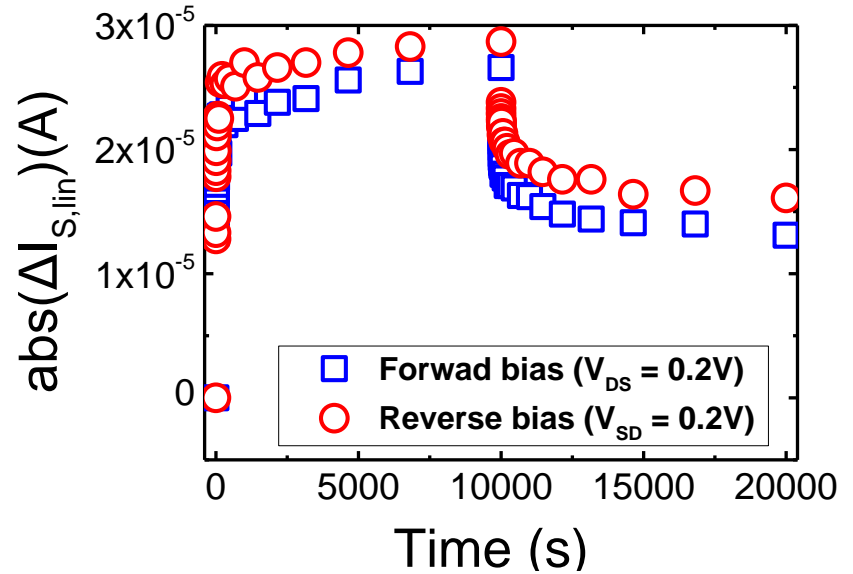
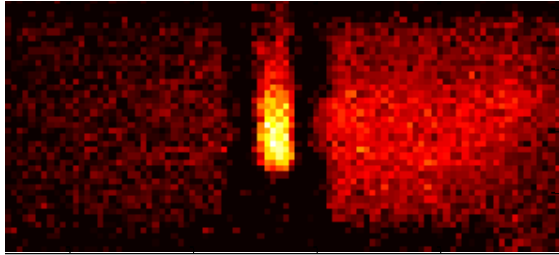
- Background: Variability/Reliability in Planar Transistors
- Self-heating in SG-FETs: An Emerging Issue
- Channel Width/Length dependence
- Reliability correlated to Variability: New Channels for MOSFET Degradation
- Conclusions

A Short History of Reliability

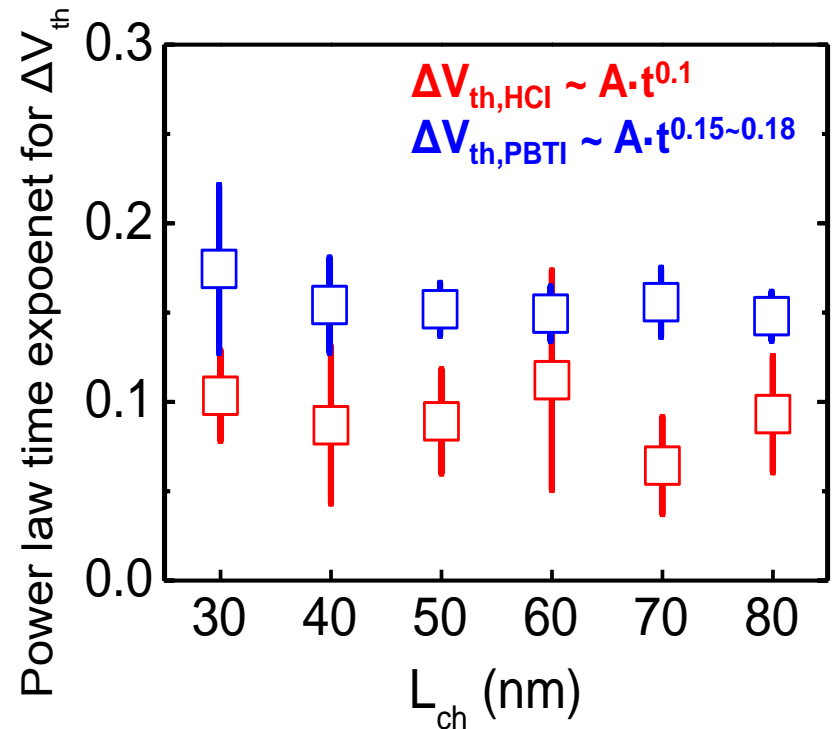
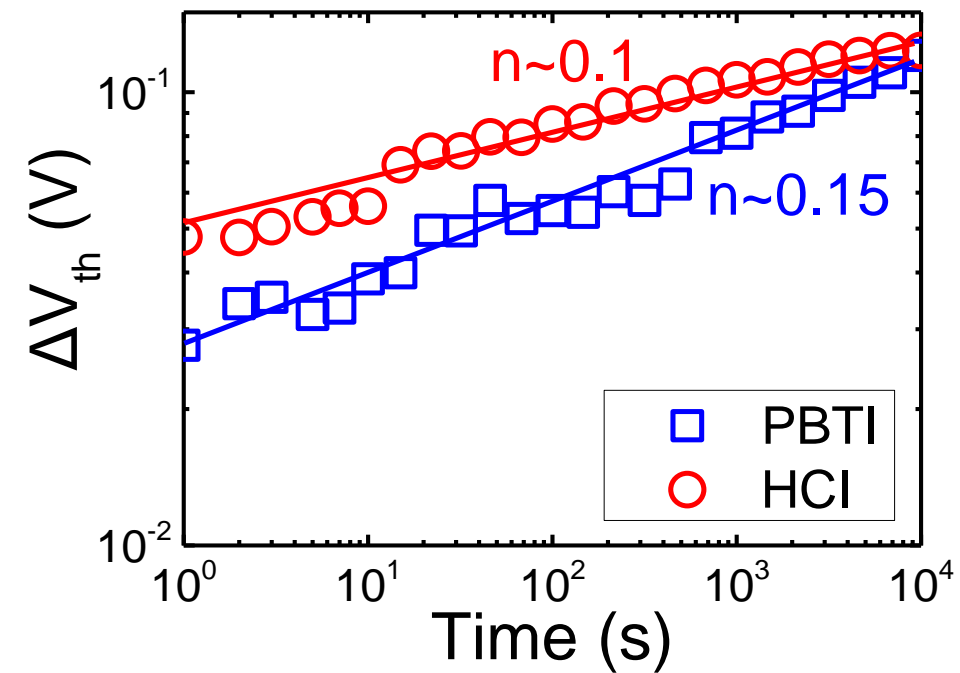


How do III-V reliability compare to the Si counterpart ?

HCl damages the drain-edge

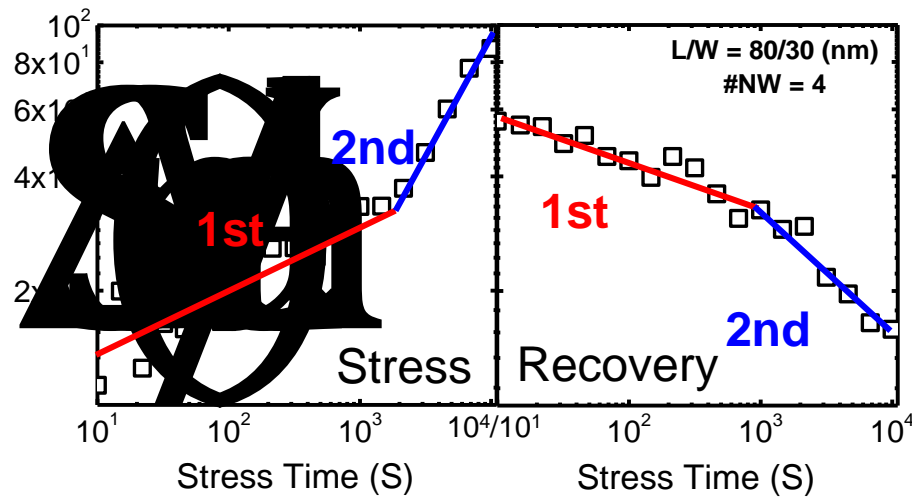
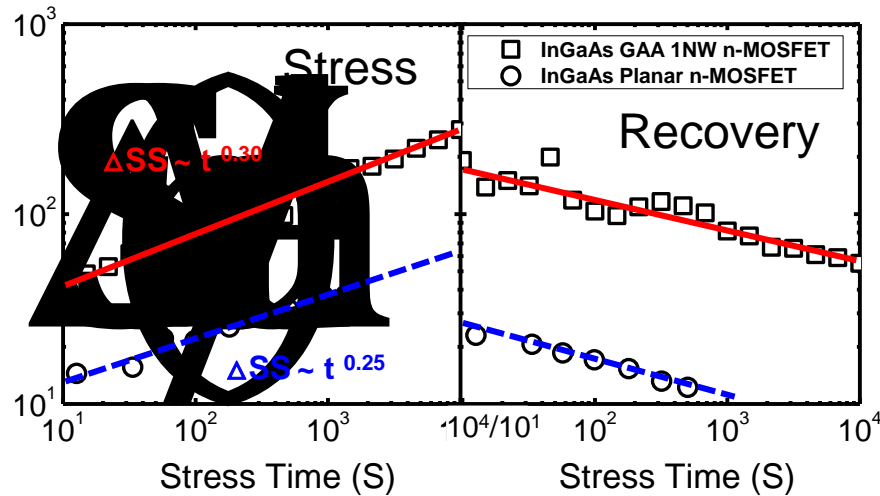


PBTI vs. HCl: ΔV_T degradation

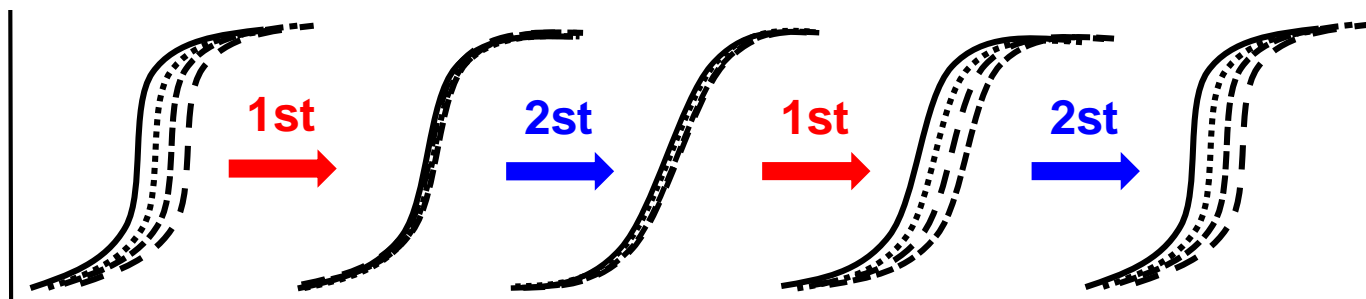
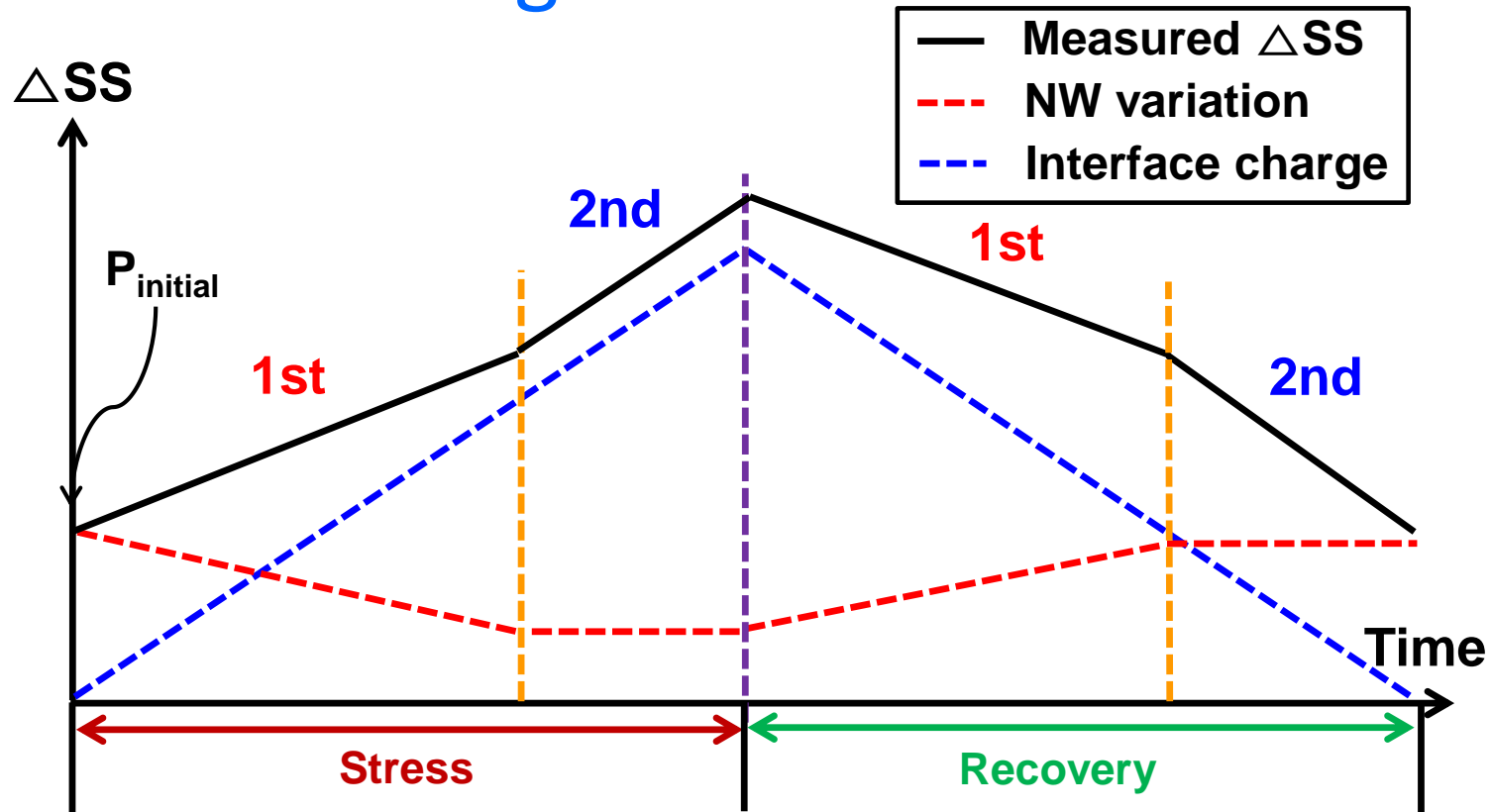


HCl dominated by trapping, PBTI by donor trap generation

Variability-Reliability: Features of the Subthreshold Slope

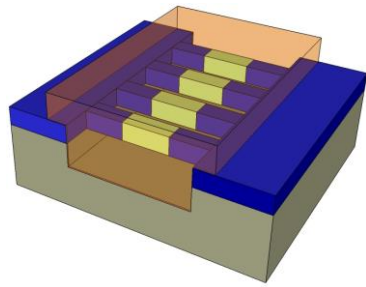


Multi-stage PBTI

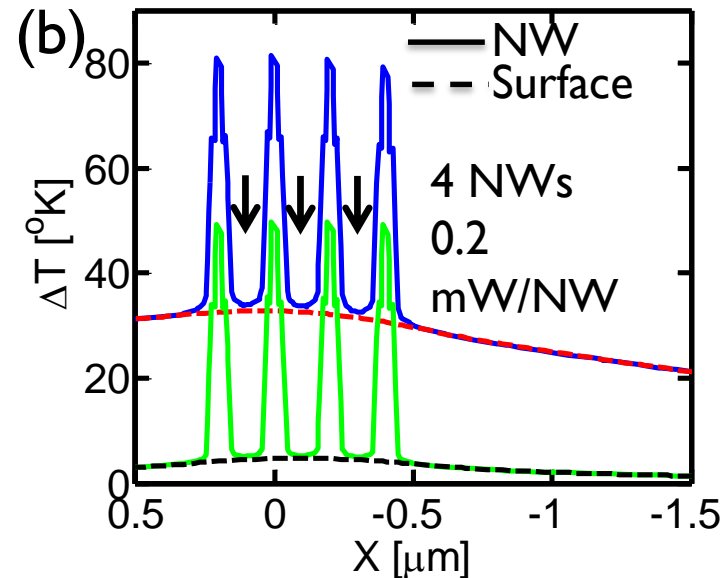
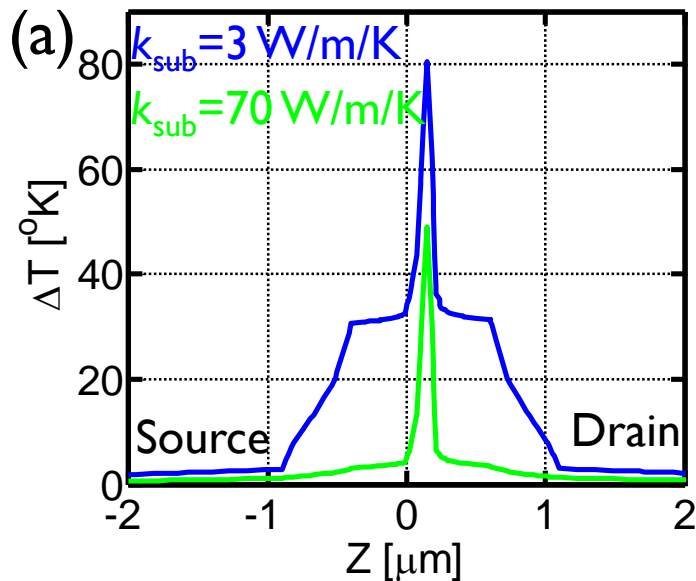
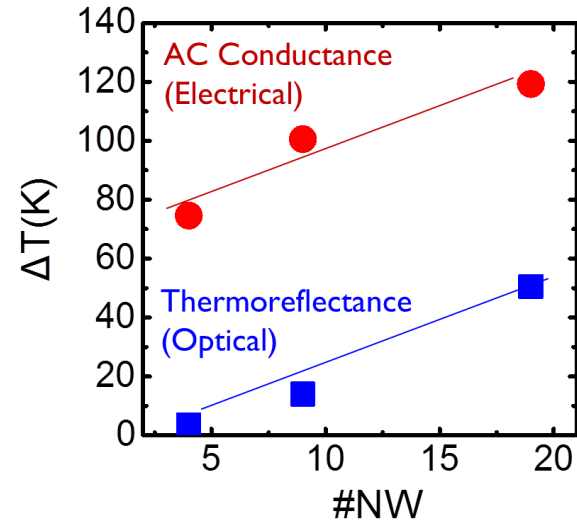


Time evolution of variation of transfer characteristic of NWs in a transistor

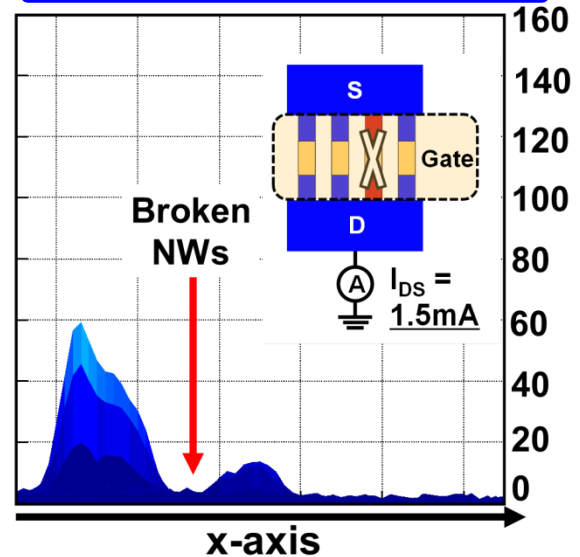
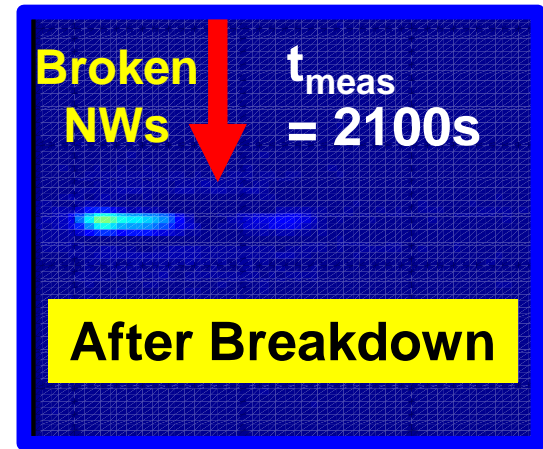
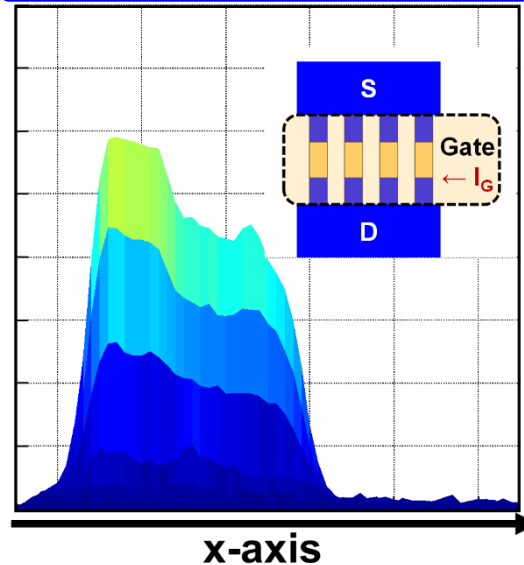
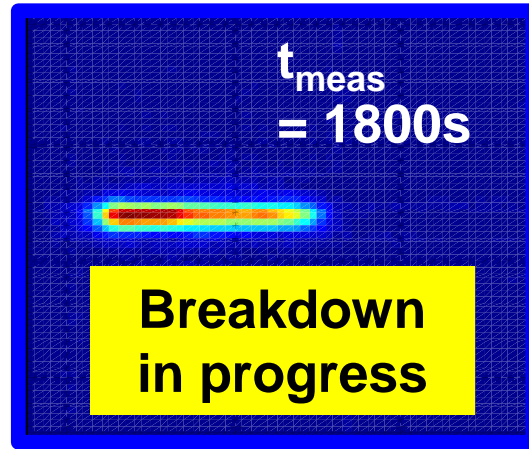
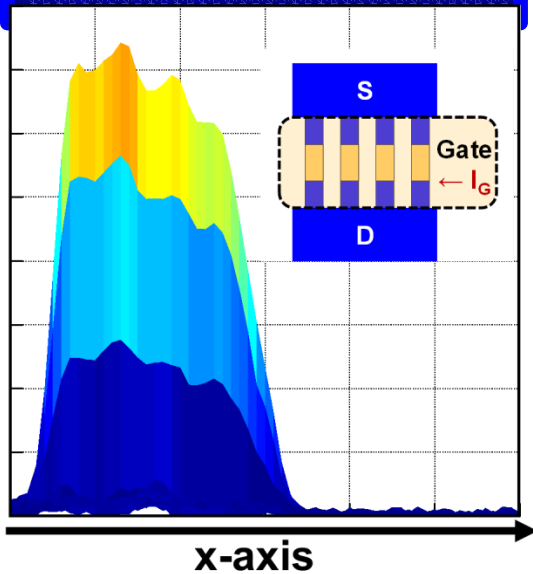
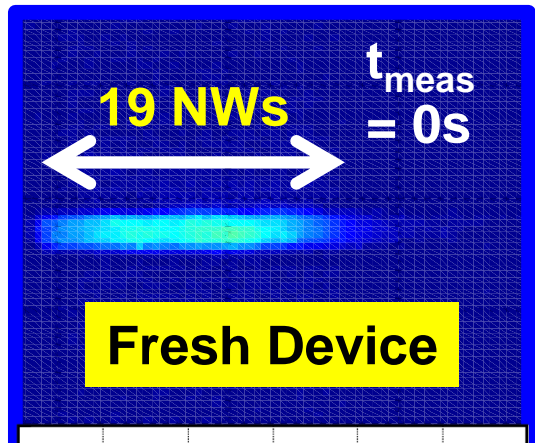
(3) TDDB: NW dictates self-heating



0.2 mW/NW



Correlated NW-dependent TDDB



TDDB depends on # of NW !

Conclusions

- Significant self-heating expected in surround gate technologies.
- This creates a new source of run-time variability, but also interesting correlation between process variability and reliability.
- Width dependence, TDDB and PBTI all require significant redefinition of design process.
- This is especially challenging for tail distribution.